



Specification

Buffered Oxide Etch 6:1

Semiconductor Grade

<u>Property</u>	<u>Specification</u>
Ammonium Fluoride (wt%)	33.6-34.6%
HF Assay (wt%)	7.08-7.38%
Aluminum	0.2 ppm maximum
Arsenic and Antimony	0.03 ppm maximum
Boron	0.2 ppm maximum
Calcium	0.2 ppm maximum
Chromium	0.1 ppm maximum
Copper	0.1 ppm maximum
Iron	0.2 ppm maximum
Lead	0.3 ppm maximum
Magnesium	0.2 ppm maximum
Manganese	0.2 ppm maximum
Nickel	0.2 ppm maximum
Potassium	0.3 ppm maximum
Sodium	0.3 ppm maximum
Tin	0.3 ppm maximum
Titanium	0.3 ppm maximum
Zinc	0.3 ppm maximum

Tested to Semi Book of Standards Process Chemicals 0307

Part Number 3309